

AP20 Rec'd PCT/PTO 09 AUG 2006

SHIGA7.053APC

PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ogata et al.  
 Appl. No. : U.S. National Phase of  
               PCT/JP2005/000660  
 Filed : Herewith  
 For : POLYMER COMPOUND,  
       PHOTORESIST COMPOSITION  
       INCLUDING THE POLYMER  
       COMPOUND, AND RESIST  
       PATTERN FORMATION  
       METHOD  
 Examiner : Unassigned  
 Group Art Unit : Unknown

## CERTIFICATE OF MAILING

I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

August 9, 2006

(Date)

Neil S. Bartfield, Ph.D., Reg. No. 79,901

PRELIMINARY AMENDMENT

Mail Stop PCT  
 Commissioner for Patents  
 P.O. Box 1450  
 Alexandria, VA 22313-1450

Dear Sir:

Prior to examination of the above-referenced application, please enter the following amendments:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** begin on page 3 of this paper.

**Remarks** begin on page 5 of this paper.